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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/749,876	12/31/2003	Christopher Gudeman	KOV-012	6305
36872	7590 02/24/2006		EXAMINER	
THE LAW OFFICES OF ANDREW D. FORTNEY, PH.D., P.C.			WALKE, AMANDA C	
	7 N. MAPLE AVENUE DG. D, SUITE 107		ART UNIT	PAPER NUMBER
FRESNO, C			1752	

DATE MAILED: 02/24/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
Office Astion Comments	10/749,876	GUDEMAN ET AL.				
Office Action Summary	Examiner	Art Unit				
	Amanda C. Walke	1752				
The MAILING DATE of this communication ap Period for Reply	pears on the cover sheet with the o	orrespondence address				
A SHORTENED STATUTORY PERIOD FOR REPL WHICHEVER IS LONGER, FROM THE MAILING D - Extensions of time may be available under the provisions of 37 CFR 1. after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period - Failure to reply within the set or extended period for reply will, by statute that the period for reply will, by statute that the period for reply will, by statute that the mailing earned patent term adjustment. See 37 CFR 1.704(b).	DATE OF THIS COMMUNICATION 136(a). In no event, however, may a reply be tir will apply and will expire SIX (6) MONTHS from e, cause the application to become ABANDONE	N. nety filed the mailing date of this communication. ED (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on 12 L	December 2005.					
2a)⊠ This action is FINAL . 2b)☐ This	☐ This action is FINAL . 2b)☐ This action is non-final.					
3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is						
closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.						
Disposition of Claims						
4) ☐ Claim(s) 1-112 is/are pending in the application 4a) Of the above claim(s) 21-112 is/are withdra 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-20 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or	awn from consideration.					
Application Papers						
9) The specification is objected to by the Examine 10) The drawing(s) filed on is/are: a) accomposed and applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the Examine 11.	cepted or b) objected to by the lead of a drawing(s) be held in abeyance. Settion is required if the drawing(s) is objected to by the lead of the drawing(s) is objected to by the lead of the drawing(s) is objected to by the lead of th	e 37 CFR 1.85(a). jected to. See 37 CFR 1.121(d).				
Priority under 35 U.S.C. § 119						
 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No. 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 						
Attachment(s) Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)						
Paper No(s)/Mail Date	6) Other:					

DETAILED ACTION

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 2. Claims 1-20 are rejected under 35 U.S.C. 102(e) as being anticipated by Hanabata et al (6,921,623).

Hanabata et al disclose an active component which is useful for forming minute patterns such as semiconductor integrated circuits using a beam, for example, ultraviolet rays or farultraviolet rays (including excimer lasers or the like); a photosensitive resin composition (resist composition) using the same; and a process for forming a pattern using the same. The combination use of an active component and a photosensitive resin composition is attributed to forming high resolution pattern with high sensitivity because of a difference in solubility in a developer between exposed area and non-exposed area, wherein a functional group is introduced into the active component [e.g., a fine or finely divided particle (an active particle) capable of being hydrophilic by eliminating a hydrophobic leaving group owing to at least light exposure, a specific metal alkoxide (an active metal alkoxide) or the polycondensate thereof (an active particle formed by polycondensation)] to cause (yield) a difference in solubility owing to light exposure, and that the combination use of the metal alkoxide or a polycondensate thereof, and a

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photosensitive resin composition, is attributed to forming high(er) resolution pattern with higher sensitivity because of reduction of impurity incorporation. The present invention was accomplished based on the above findings. The claimed particle appears to meet the instant claim limitations, thus the instant claims are anticipated.

Response to Arguments

3. Applicant's arguments filed 12/12/2005 have been fully considered but they are not persuasive. Applicant has argued that the particles of Hanabata et al do not teach the use of conductive metals. While the applicant is correct that the reference prefers that the metal be silicon, it clearly teaches the use of aluminum and transition metals as well among the small list of choices for M. When M is aluminum or a transition metal, the particle would meet the instant claim limitations, and such a particle is contemplated by the reference despite its preference for a silicon/ transparent particle. The reference also teaches particles comprising gold, silver, copper, platinum, and aluminium. Thus the reference meets the instant claim limitations for a patternable material comprising nanopartiles as instantly claimed.

It has been noted by the examiner that the applicant has amended claims that have been withdrawn. As these claims have been withdrawn previously, they will remain so despite the amendment.

Conclusion

4. THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO

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MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Amanda C. Walke whose telephone number is 571-272-1337. The examiner can normally be reached on M-R 5:30-4.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Cynthia Kelly can be reached on 571-272-1526. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Amanda C Walke Examiner

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ACW February 21, 2006